Fig.1

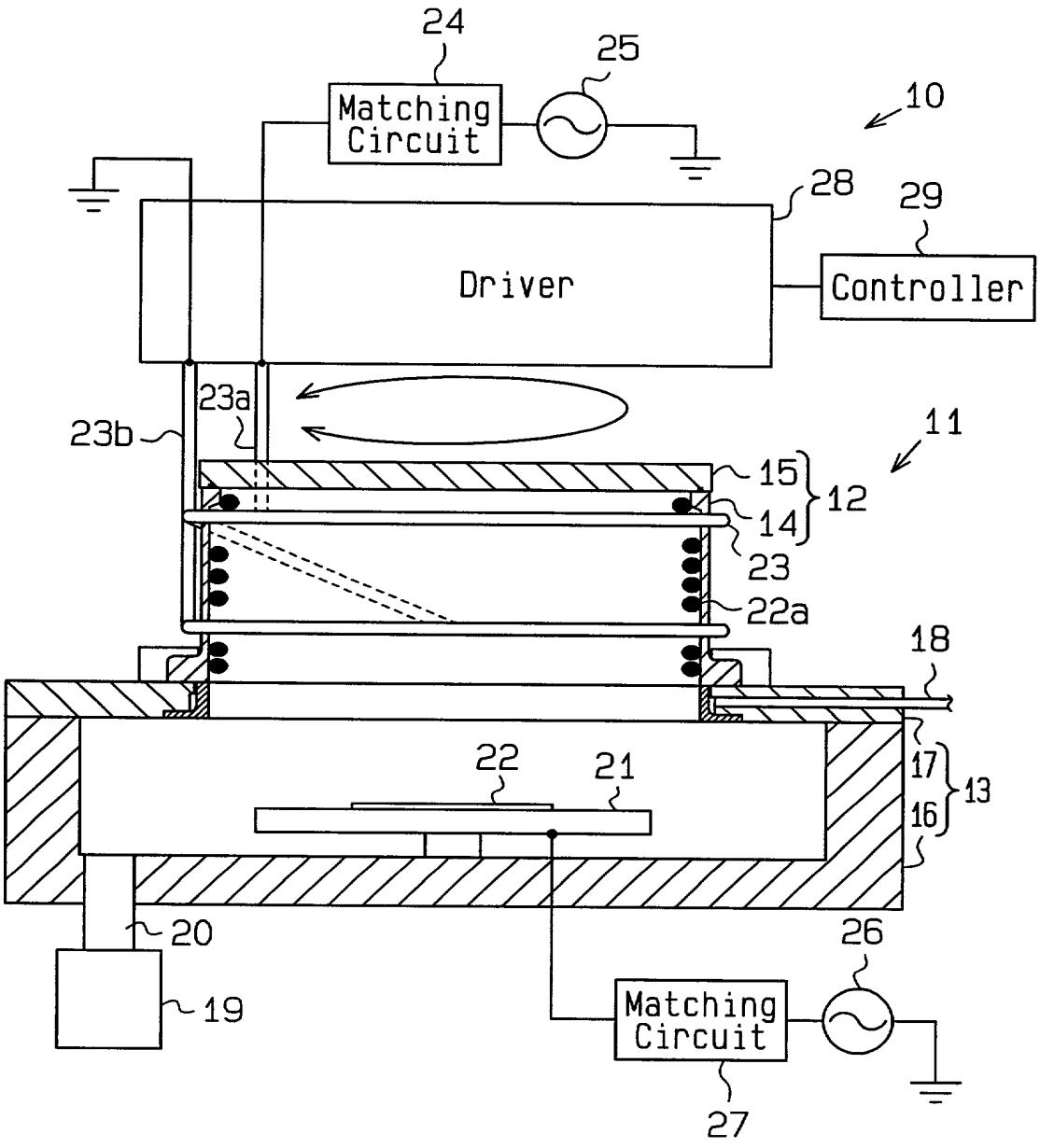
24
25
Matching Circuit
10
28
29
Driver
Controller
23a
23b
11
15
12
14
23
22a
18
22
21
17
13
16
20
26
19
Matching Circuit
27

Fig.2a

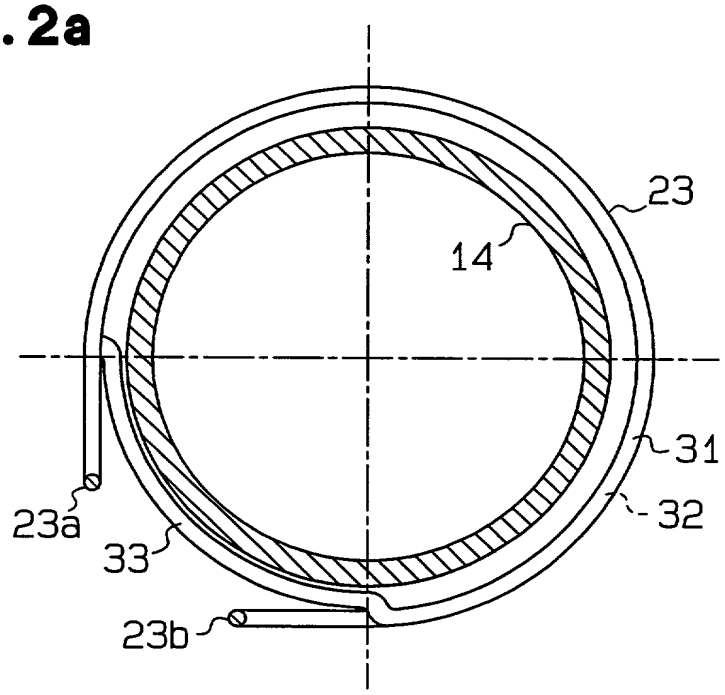

Fig.2b

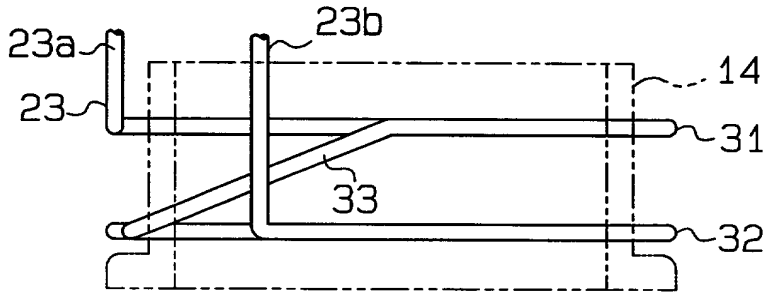

Fig.3a

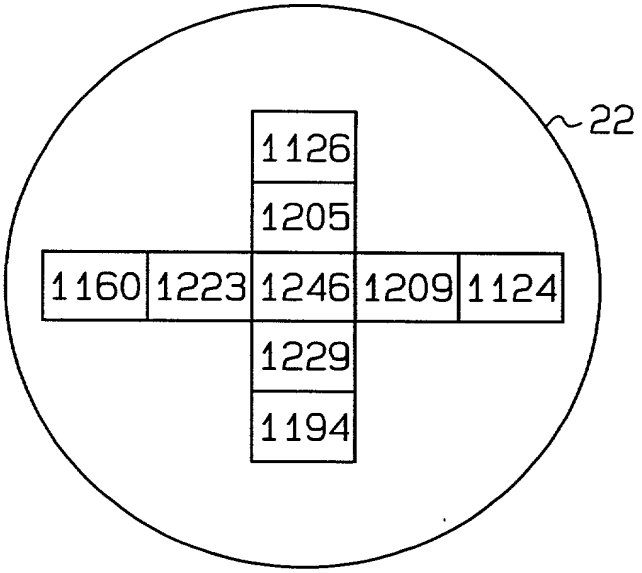

Fig.3b
(Prior Art)

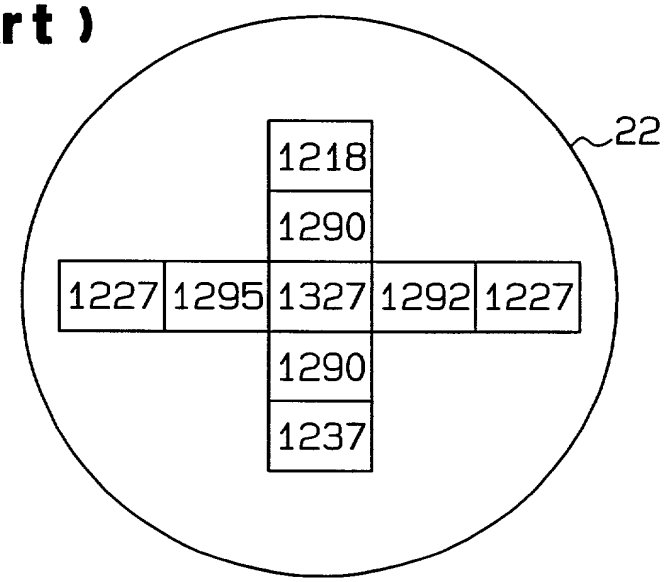

Fig.4

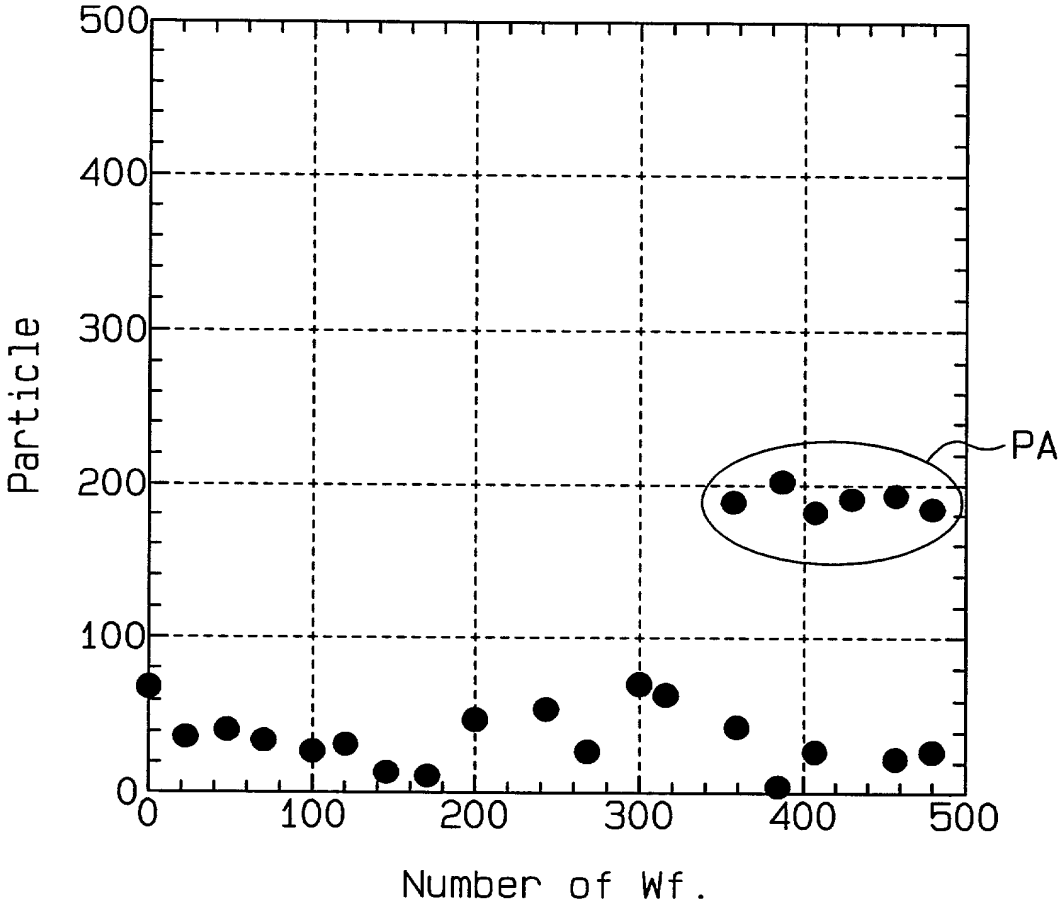
500
400
300
200
100
0
Particle
0
100
200
300
400
500
Number of Wf.
PA

Fig.5

Numbers of wafers rotation	Rotation rate (rpm)	Number of processed wafers	Particle size	Initial particle number	Particle number after processing	Difference	TOTAL
0	0	25	S	19	26	+7	+31
			SM	1	12	+11	
			M	0	13	+13	
			L	0	0	0	
		100	SM	10	18	+8	+17
			SM	2	6	+4	
			M	3	8	+5	
			SM	0	0	0	
Approx. 3.75	Approx. 0.52	25	S	24	59	+35	+43
			SM	3	5	+2	
			M	6	12	+6	
			L	0	0	0	
		100	S	15	15	0	+13
			SM	2	6	+4	
			M	6	15	+9	
			L	0	0	0	
		150	S	21	5	-16	-18
			SM	0	3	+3	
			M	7	2	-5	
			L	0	0	0	
Approx. 37	Approx. 0.054	25	S	2	23	+21	+33
			SM	1	8	+7	
			M	8	13	+5	
			L	0	0	0	
		100	S	37	13	-24	-37
			SM	15	6	-9	
			M	15	10	-5	
			L	0	1	+1	
Approx. 148	Approx. 0.0135	25	S	8	26	+18	+29
			SM	4	7	+3	
			M	13	21	+8	
			L	0	0	0	
		100	S	22	19	+3	+10
			SM	1	8	+7	
			M	3	9	+6	
			L	0	0	0	
		150	S	12	19	+7	+12
			SM	0	3	+3	
			M	3	5	+2	
			L	0	0	0	

Fig.6

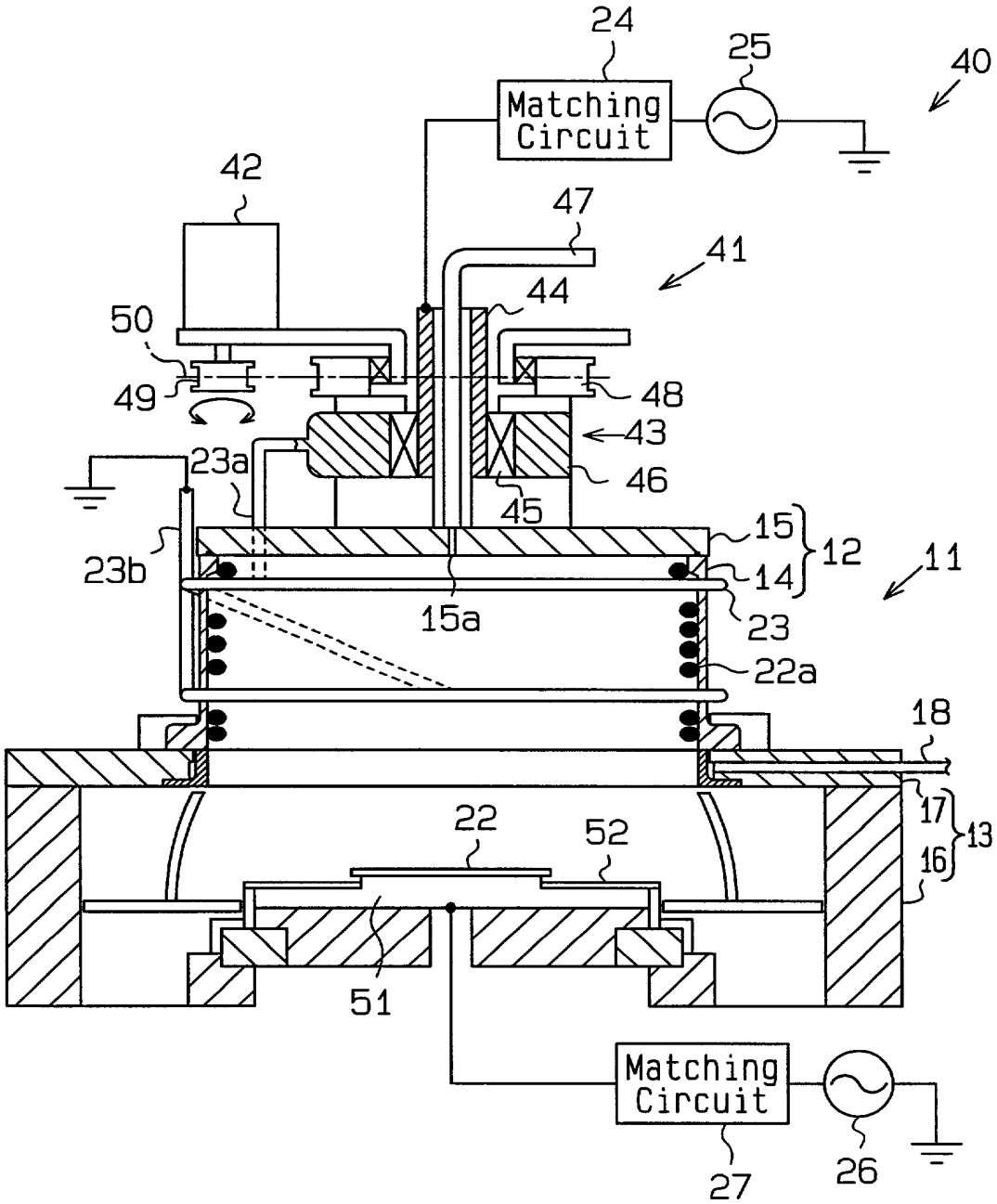
24
25
40
Matching Circuit
42
47
41
44
50
49
48
43
23a
46
45
15
12
11
23b
14
15a
23
22a
18
17
13
22
52
16
51
Matching Circuit
27
26

Fig.7a

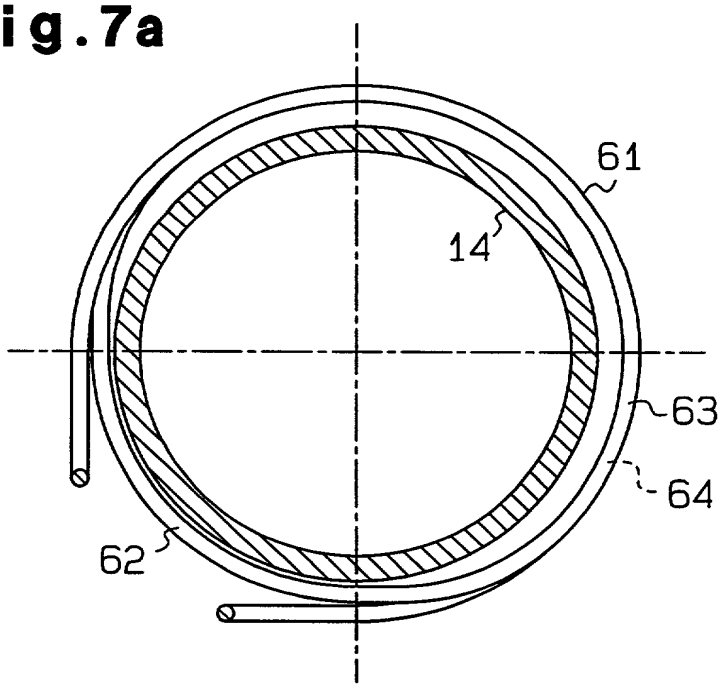

Fig.7b

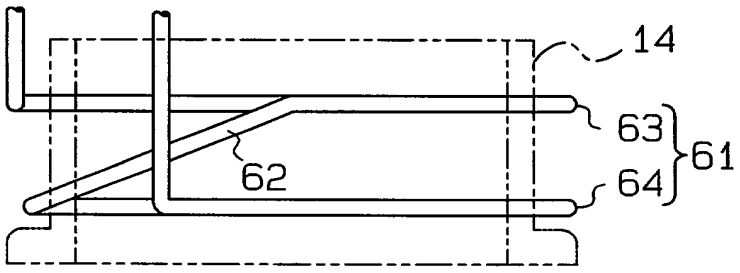

Fig.8a

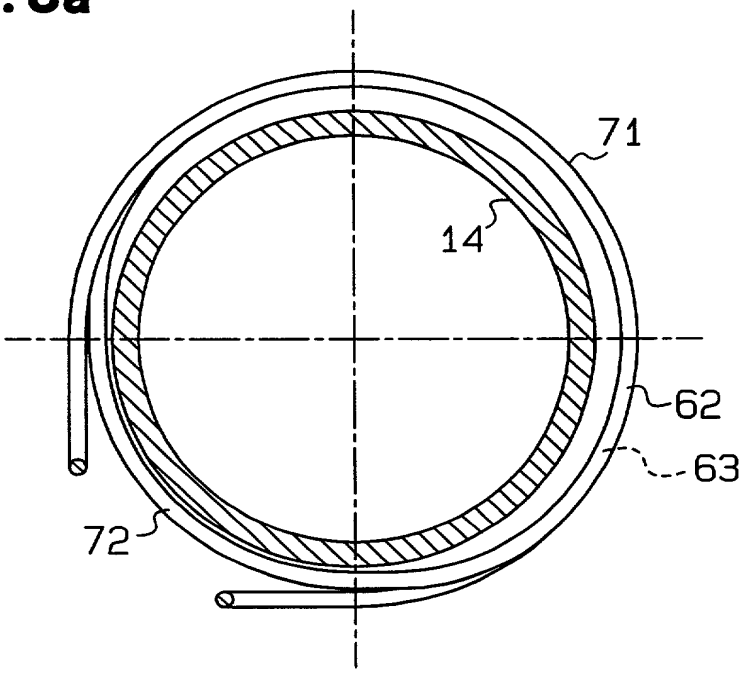

Fig.8b

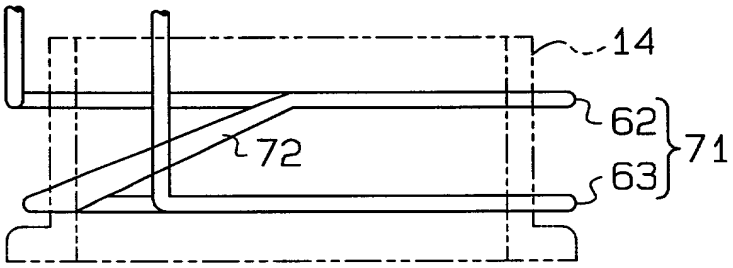

Fig.9a

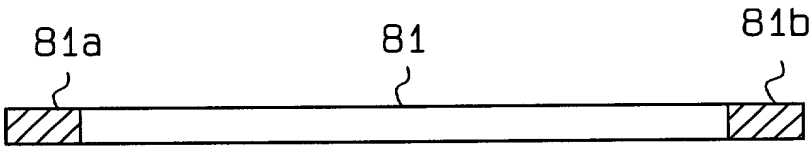

Fig.9b

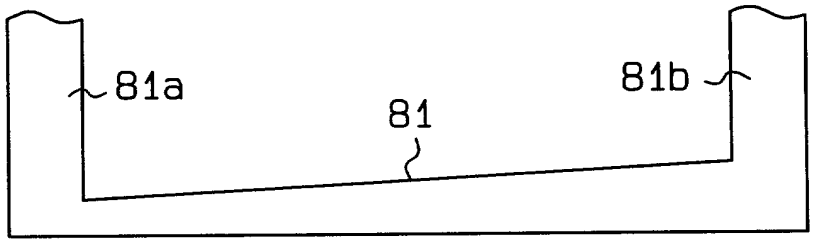

Fig.10a

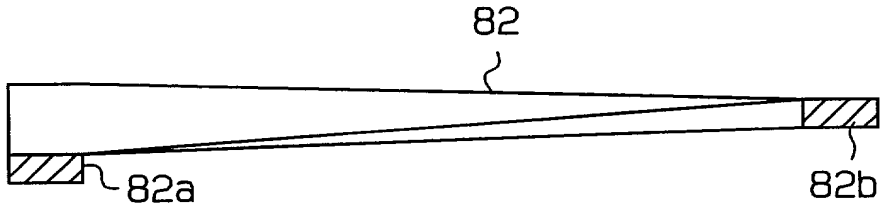
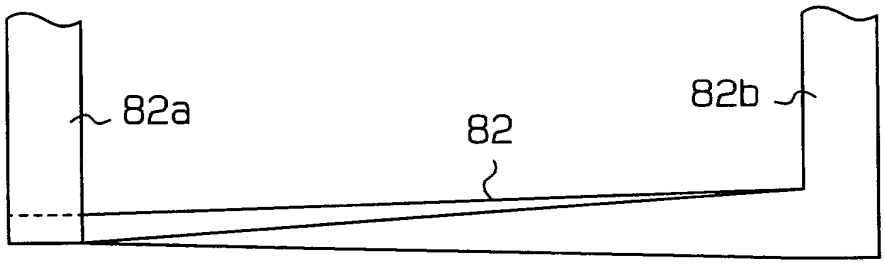
Fig.10b